

Notice of References CitedApplication/Control No.
09/838,513Applicant(s)/Patent Under
Reexamination
CHEN ET AL.Examiner
Julio J. MaldonadoArt Unit
2823

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U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,937,325	08-1999	Ishida	438/655
	B	US-			
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	D	US-			
	E	US-			
	F	US-			
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FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Mouroux, Alette; The Reactive Formation of TiSi ₂ in the Presence of Refractory Metals (from V to W), Royal Institute of Technology, Department of Electronics, Stockholm 1,999.
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	W	
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a))
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